

ABSTRACT

The cleaner of the present invention contains, as an active ingredient, a polyphosphoric-acid-urea condensate or phosphoric-acid-urea polymer which is a reaction product from orthophosphoric acid and urea and is used for cleaning a metal surface and/or a glass surface in at least one process of a semiconductor device production process and a liquid crystal device production process. According to the present invention, an etching residue and impurities on metal (including semimetal) and glass surfaces can be cleaned off with high environmental and working safety and effectively without causing the problem of metal corrosion.